Hsien-Wen Wan

List of Publications by Year in descending order

Source: https://exaly.com/author-pdf/6174368/publications.pdf

Version: 2024-02-01

1684188 1474206 22 96 5 9 citations h-index g-index papers 22 22 22 75 all docs docs citations times ranked citing authors

#	Article	IF	CITATIONS
1	Attainment of low subthreshold slope in planar inversion-channel InGaAs MOSFET with in situ deposited Al ₂ O ₃ /Y ₂ O ₃ as a gate dielectric. Japanese Journal of Applied Physics, 2022, 61, SC1018.	1.5	4
2	Low thermal budget epitaxial lift off (ELO) for Ge (111)-on-insulator structure. Japanese Journal of Applied Physics, 2022, 61, SC1024.	1.5	1
3	In-situ deposited HfO ₂ and Y ₂ O ₃ on epi-Si/p-Geâ€"a comparative study of the interfacial properties and reliability. Japanese Journal of Applied Physics, 2022, 61, SC1074.	1.5	2
4	A Synchrotron Radiation Photoemission Study of SiGe(001)- $2\tilde{A}$ -1 Grown on Ge and Si Substrates: The Surface Electronic Structure for Various Ge Concentrations. Nanomaterials, 2022, 12, 1309.	4.1	2
5	High-Ge-Content Si _{1<i>–x</i>} Ge _{<i>x</i>} Gate Stacks with Low-Temperature Deposited Ultrathin Epitaxial Si: Growth, Structures, Low Interfacial Traps, and Reliability. ACS Applied Electronic Materials, 2022, 4, 2641-2647.	4.3	1
6	(Invited) Thin Epitaxial Single-Crystal Si on Sige Followed By in-Situ Deposition of High-k Dielectrics – Novel Gate Stacks for Achieving Extremely Low D _{it} and Highly Reliable SiGe MOS. ECS Meeting Abstracts, 2022, MA2022-01, 1067-1067.	0.0	0
7	Microscopic Views of Ge Segregation and Scavenging Ge on Thin Si on Epi-Ge(001). ECS Meeting Abstracts, 2022, MA2022-01, 1053-1053.	0.0	O
8	Low-Temperature-Grown Single-Crystal Si Epitaxially on Ge, Followed by Direct Deposition of High-κ Dielectrics–Attainment of Low Interfacial Traps and Highly Reliable Ge MOS. ACS Applied Electronic Materials, 2021, 3, 2164-2169.	4.3	8
9	<i>In situ</i> Y2O3 on <i>p</i> -In0.53Ga0.47Asâ€"Attainment of low interfacial trap density and thermal stability at high temperatures. Applied Physics Letters, 2021, 118, .	3.3	6
10	Oxidation and hydrogenation of SiGe(0 0 1)- $2\hat{A}$ — \hat{A} 1 at room temperature and in situ annealing: A synchrotron radiation photoemission study. Applied Surface Science, 2021, 569, 150962.	6.1	0
11	Low-temperature grown single-crystal Si on $\langle i \rangle$ epi $\langle i \rangle$ Ge(001)-2 \tilde{A} — 1 and its oxidation: electronic structure study via synchrotron radiation photoemission. Applied Physics Express, 2020, 13, 085504.	2.4	7
12	Surface electronic structure of Si _{1\hat{a}'<i>x</i>} Ge <i>_x</i> (001)-2 \hat{A} — 1: a synchrotron radiation photoemission study. Applied Physics Express, 2020, 13, 095503.	2.4	6
13	Fundamental Understanding of Oxide Defects in HfO2 and Y2O3 on GaAs(001) with High Thermal Stability., 2019,,.		1
14	BTI Characterization of MBE Si-Capped Ge Gate Stack and Defect Reduction via Forming Gas Annealing. , 2019, , .		3
15	Microscopic Views of Atomic and Molecular Oxygen Bonding with epi Ge(001)-2 \tilde{A} — 1 Studied by High-Resolution Synchrotron Radiation Photoemission. Nanomaterials, 2019, 9, 554.	4.1	5
16	Epitaxy of High-Quality Single-Crystal Hexagonal Perovskite YAlO ₃ on GaAs(111)A Using Laminated Atomic Layer Deposition. Crystal Growth and Design, 2019, 19, 2030-2036.	3.0	3
17	Atomic Nature of the Growth Mechanism of Atomic Layer Deposited High- \hat{l}^2 Y ₂ O ₃ on GaAs(001)-4 \tilde{A} — 6 Based on in Situ Synchrotron Radiation Photoelectron Spectroscopy. ACS Omega, 2018, 3, 2111-2118.	3.5	8
18	Exciton Localization of High-Quality ZnO/Mg _{<i>x</i>} Zn _{1â€"<i>x</i>} O Multiple Quantum Wells on Si (111) with a Y ₂ O ₃ Buffer Layer. ACS Applied Nano Materials, 2018, 1, 3829-3836.	5.0	5

#	Article	IF	CITATIONS
19	Atomic layer deposited single-crystal hexagonal perovskite YAlO3 epitaxially on GaAs(111)A. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, 01B123.	2.1	2
20	Perfecting the Al2O3/In0.53Ga0.47As interfacial electronic structure in pushing metal-oxide-semiconductor field-effect-transistor device limits using <i<math>\timesin-situatomic-layer-deposition. Applied Physics Letters, 2017, 111, .</i<math>	3.3	15
21	Surface electronic structure of epi germanium (001)-2 $ ilde{A}-1$. Applied Physics Express, 2017, 10, 075701.	2.4	16
22	Scavenging Segregated Ge on Thin Single-Crystal Si Epitaxially Grown on Ge. ACS Applied Electronic Materials, 0, , .	4.3	1